

2

AD-A209 698

OFFICE OF NAVAL RESEARCH

Research Contract N00014-87-K-0014

R&T Code 413a001

Technical Report No. 20

A STUDY OF THERMODYNAMIC PHASE STABILITY OF INTERMETALLIC
THIN FILMS OF Pt_2Ga , $PtGa$ AND $PtGa_2$ ON GALLIUM ARSENIDE

by

Young K. Kim, David K. Shuh,[†] R. Stanley Williams,[†]
Larry P. Sadwick* and Kang L. Wang*

To be published in

Proc. Mat. Res. Soc. Spring Symp., San Diego, 1989

University of California, Los Angeles

[†]Department of Chemistry & Biochemistry and Solid State Science Center
Los Angeles, CA 90024-1569

and

*Department of Electrical Engineering
Los Angeles, CA 90024-1594

SDIC
ELECTR
JUN 22 1989
H

July 1, 1989

Reproduction in whole or part is permitted for any purpose of the United States Government.

This document has been approved for public release and sale;
its distribution is unlimited

89 6 21 022

A STUDY OF THERMODYNAMIC PHASE STABILITY OF INTERMETALLIC THIN FILMS OF Pt₂Ga, PtGa AND PtGa₂ ON GALLIUM ARSENIDE

Young K. Kim*, David K. Shuh*, R. Stanley Williams*, Larry P. Sadwick** and Kang L. Wang**

*Department of Chemistry and Biochemistry and Solid State Science Center, University of California, Los Angeles, California 90024-1569

**Department of Electrical Engineering Device Research Laboratory, University of California, Los Angeles California 90024

ABSTRACT

Epitaxial thin films of three different Pt-Ga intermetallic compounds have been grown on GaAs by molecular beam epitaxy (MBE). The resultant films have been annealed at various temperatures and then examined using X-ray two-theta diffraction. Both PtGa₂ and PtGa thin films are chemically stable on GaAs under 1 atmosphere of N₂ up to 450°C and 600°C, respectively. Thin films of Pt₂Ga react with GaAs at temperatures as low as 200°C to form phases with higher Ga concentration.

Introduction

The interface chemistry of metal-semiconductor contacts plays an important role in controlling the electrical properties of Schottky barriers and Ohmic contacts [1]. Chemically stable contacts must be formed at the metal-semiconductor interface in order for electronic devices to survive processing procedures and operate reliably in harsh environment applications for long periods of time [2,3]. A possible solution for this interface problem would be to use a contact metal that can coexist with GaAs in bulk thermodynamic equilibrium. Such stable metals can be found by examining ternary phase diagrams, such as the Pt-Ga-As system, which was experimentally elucidated by Tsai et. al. [4] and is illustrated in Fig. 1. The existence of a pseudobinary tie-line between two compounds in the ternary phase diagram implies that the compounds will not react with each other in a closed system, i.e. the bulk compounds are in thermodynamic equilibrium with respect to each other. Therefore, from Fig. 1 it can be expected that PtGa and PtGa₂ will form stable contacts with GaAs but that Pt₂Ga will not. In the present study, these expectations are tested by investigating the phase composition of thin films of Pt₂Ga, PtGa and PtGa₂ on GaAs after annealing to various temperatures.

Film Growth

The Pt-Ga intermetallic films were grown in a MBE chamber with a base pressure of 2×10^{-10} torr and a deposition pressure of approximately 4×10^{-9} torr. The two inch GaAs substrates were introduced via a cryopumped load lock system and mounted on a modified manipulator equipped with radiative heating elements. The samples were cleaned in-situ by heating to a temperature of approximately 525°C. The platinum was evaporated using a Varian 3 KW electron beam evaporator and the gallium was obtained from a Knudsen cell constructed of a pyrolytic boron nitride (PBN) crucible with a tantalum heating element. The fluxes of platinum and gallium were initially tuned to the proper stoichiometry based on empirical knowledge. PtGa₂ can be visually identified by its characteristic golden color, since PtGa₂ is the only Pt-Ga phase that has a band structure similar to that of elemental gold [5]. Neither PtGa nor Pt₂Ga can be easily identified by color. The flux rate from the gallium source was stabilized by temperature control circuits that ensured a constant flux rate for each source power setting. Subsequent depositions have been controlled with a Leybold-Inficon IC-6000 crystal monitor system. To obtain single phase Pt-Ga intermetallic films, the flux ratio of gallium to platinum was adjusted to be slightly Ga rich. Co-evaporation of each Pt-Ga intermetallic proceeded with the substrate held at temperatures ranging from near room temperature to over 500°C at epilayer growth rates ranging from approximately 0.5 to 5 microns/hour.

Composition Analysis

XRD patterns of the films were taken on a Phillips X-ray powder diffractometer, which was interfaced to a microcomputer that controlled the scan rate and collected data at 0.1° intervals with a counting time of 10 seconds at each angle. The total time required for a complete scan (2θ from 10° to 100°) was about 3 hours and the typical signal-to-noise ratio for a strong diffraction peak was 30 to 1. The d spacings of the PtGa₂ and Pt₂Ga thin films were checked against a reference tabulation [6] to ensure that they were identified correctly. As

no known PtGa JCPDS data exists, the known d-spacings of PtGa [7] were compared with values calculated from the diffraction pattern of the thin film and were found to agree closely. The thin films were annealed for twenty minutes in a quartz tube furnace under a nitrogen atmosphere for temperatures ranging from 100°C to 800°C. In this paper, we present XRD results of annealing studies of the Pt-Ga intermetallic single phase thin films. A complete characterization of these films, including Auger electron spectroscopy (AES) and X-ray photoemission spectroscopy (XPS), will be presented elsewhere [8].

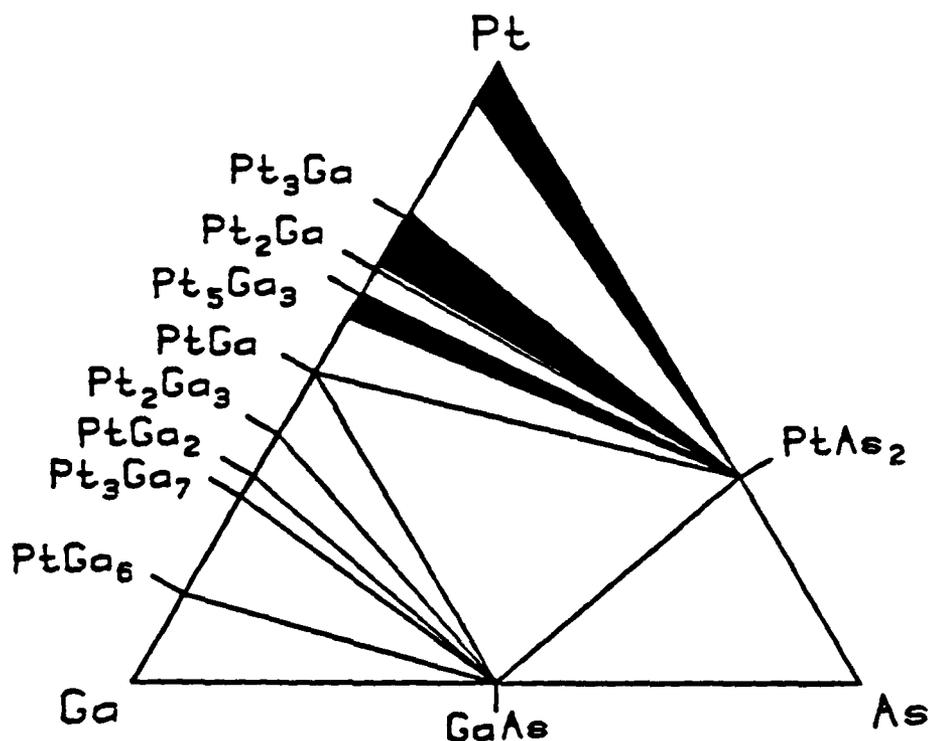


Fig. 1. Solidus portion of the Pt-Ga-As ternary phase diagram at 25°C.

Results and discussion

The grown films were specular, both to the eye and by optical microscopy. Fig. 2 shows typical powder XRD patterns of the three types of intermetallic single phase Pt-Ga thin films grown on GaAs (001) in the as-deposited state. The PtGa and Pt₂Ga thin films have a dominant (210) and (112) reflection, respectively. The PtGa₂ thin films displayed roughly equal intensity (111), (220) and (311) reflections. This would seem to imply that the crystal quality of PtGa and Pt₂Ga thin films is better than that of PtGa₂ films in spite of larger lattice mismatches. XRD patterns of a sample of Pt₂Ga on GaAs annealed to 500°C are shown in Fig. 3. Even at 200°C, a new peak corresponding to the PtGa (210) reflection begins to appear at $2\theta = 41.4^\circ$. In the diffraction patterns of the film heated to high temperatures, new phases, such as PtGa₂ and PtAs₂, begin to form at 300°C and all peaks corresponding to the Pt₂Ga phase eventually disappeared at 500°C. According to the Pt-Ga-As ternary phase diagram, Pt₂Ga is expected to react with GaAs to produce PtAs₂ and PtGa, because there is no tie-line between Pt₂Ga and GaAs. However, annealing in an open system may cause As evaporation resulting from thermal decomposition of PtAs₂ and GaAs. With further loss of As, other Pt-Ga intermetallic compounds, such as PtGa₂ and Pt₃Ga₇, may be produced. This prediction agrees very well with the experimental results; all the peaks correspond to PtGa, PtGa₂, Pt₃Ga₇ and PtAs₂ in the diffraction pattern of the Pt₂Ga thin films on GaAs annealed to 500°C.

Fig. 4 shows XRD patterns of PtGa on a GaAs sample in the as-deposited state and after annealing at various temperatures for 20 minutes each. The diffraction pattern of the PtGa film annealed to 200°C shows that a small peak corresponding to Pt₂Ga (112) beside the PtGa (210) disappeared and the other PtGa peaks became sharper and more intense. This implies that a small amount of unstable Pt₂Ga phase in the PtGa thin film reacted with extra Ga in the film or with the substrate. Annealing improves the crystallinity of the PtGa

Codes
/or

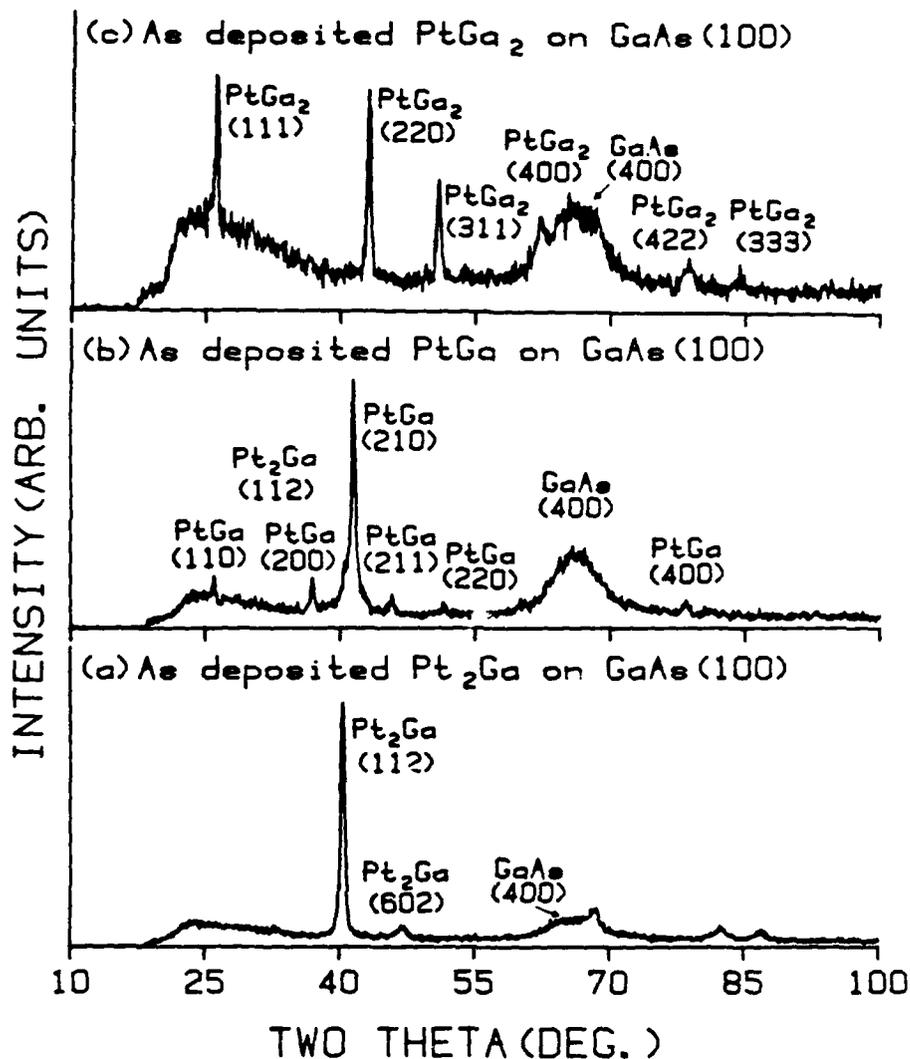


Fig. 2. XRD patterns of the three types of intermetallic single phase Pt-Ga thin films grown on GaAs (100) in the as-deposited state: (a) as-deposited Pt_2Ga on GaAs; (b) as-deposited PtGa on GaAs; (c) as-deposited $PtGa_2$ on GaAs.

film, since the signal-to-background ratio in the XRD patterns begins to increase as annealing temperature goes up. The diffraction patterns for the PtGa film annealed from 300°C to 600°C were essentially identical, but the signal-to-background ratio began to decrease. Annealing in an open system, such as in vacuum or under inert gas, may cause both $PtAs_2$ and GaAs to decompose thermally to produce gas phase As species. Therefore, in this case, the PtGa thin film starts to become Ga rich and $PtGa_2$ and Pt_3Ga_7 are produced, which coexist with PtGa and GaAs. Fig. 5 shows XRD patterns of a sample of $PtGa_2$ on GaAs heated to 100°C, 300°C, 450°C and 500°C, respectively, along with the pattern of an as-deposited film. The diffraction patterns for the sample were essentially identical up to 400°C. A new peak corresponding to the Pt_3Ga_7 (322) reflection begins to appear in XRD patterns of the sample annealed in the range of 450°C to 500°C. It is possible the $PtGa_2$ phase begins to react with extra Ga due to As evaporation from GaAs upon annealing.

Conclusions

Single phase thin films of Pt_2Ga , PtGa, and $PtGa_2$ have been successfully grown on GaAs by MBE. The results of annealing studies are in good agreement with the Pt-Ga-As ternary phase diagram. $PtGa_2$ and PtGa films are chemically stable on GaAs up to 450°C and 600°C, respectively. However, the Pt_2Ga films start

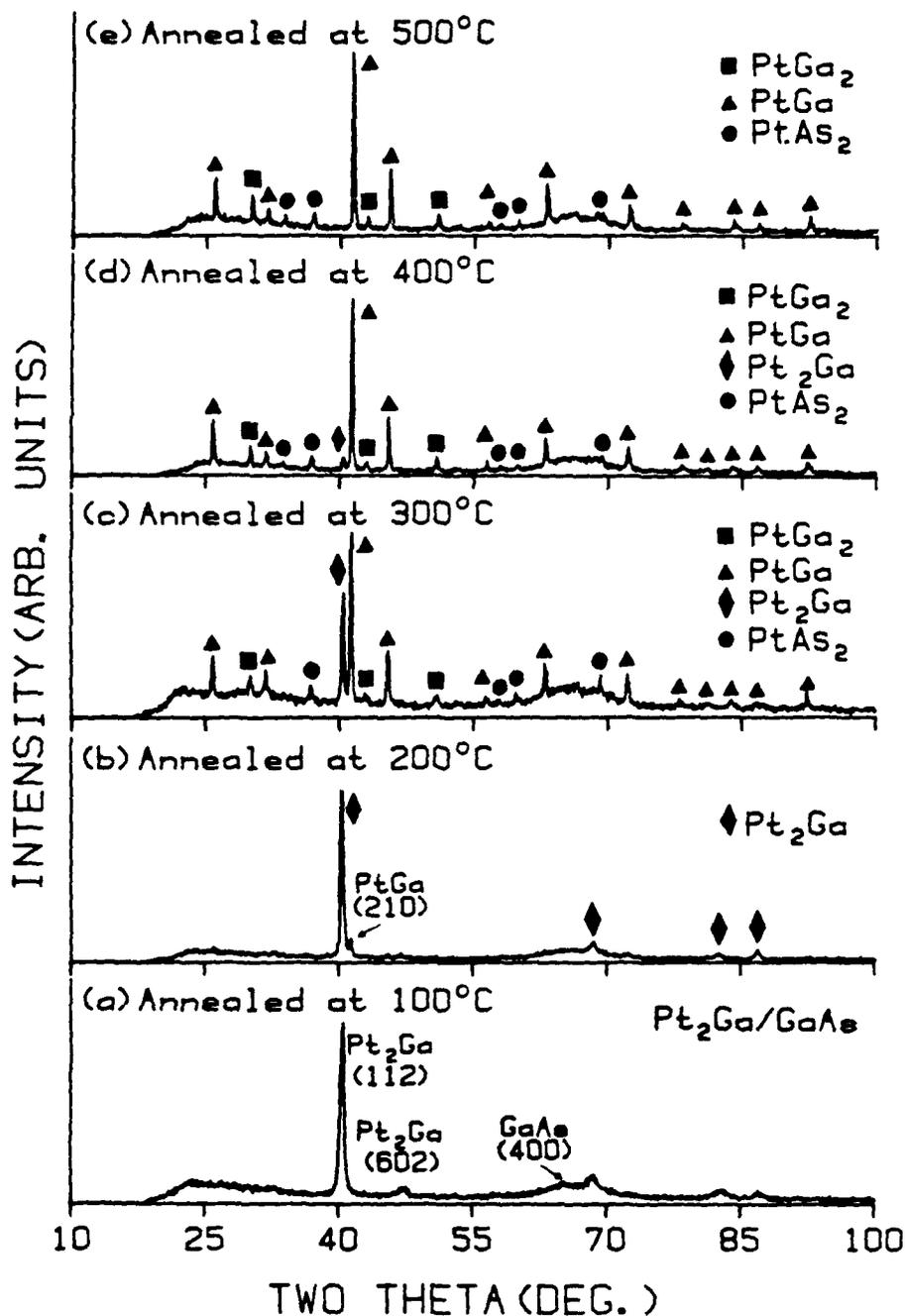


Fig. 3. XRD patterns of Pt₂Ga thin films on GaAs(100) for sample annealed to (a) 100°C, (b) 200°C, (c) 300°C, (d) 400°C and (e) 500°C.

to react with GaAs even at temperatures of 200°C to produce PtGa, PtGa₂, Pt₃Ga₇ and PtAs₂ at temperatures of 500°C. It has been shown here that the thermodynamics of bulk materials can be used to control the chemistry at the metal/semiconductor interface. In order to understand the Pt-Ga intermetallic system further, several additional studies including annealing studies under As ambient, temperature dependent TEM and transport measurements of various intermetallic Pt-Ga phases grown by MBE still need to be carried out.

Acknowledgements

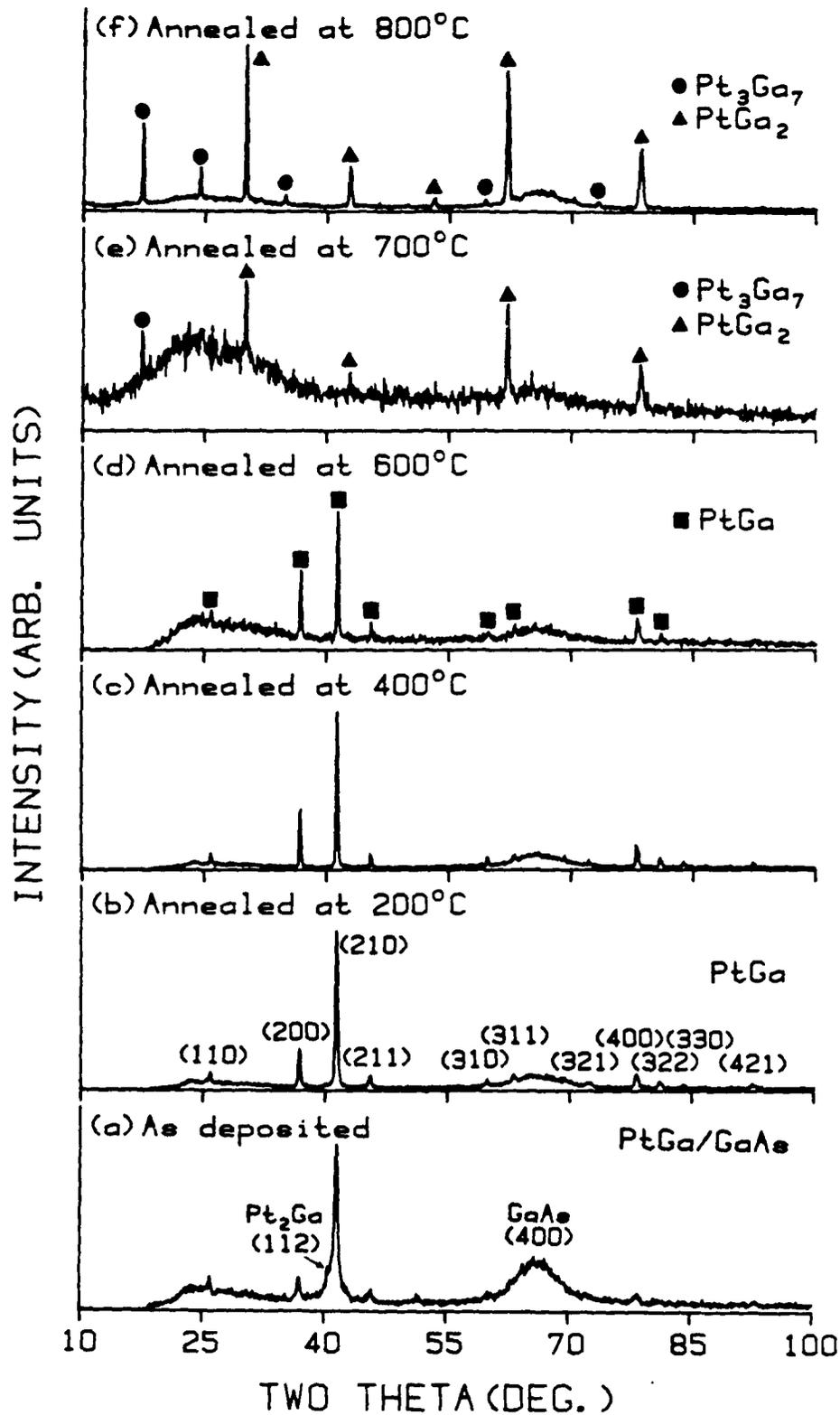


Fig. 4. XRD patterns of PtGa thin films on GaAs (100) for (a) the as-deposited film and after the sample was annealed to (b) 200°C, (c) 400°C, (d) 600°C, (e) 700°C and (f) 800°C.

This research was supported in part by the Office of Naval Research, the University of California MICRO program, and Hughes Air Craft Company. RSW would also like to thank the Henry and Camille Dreyfus Foundation for partial support.

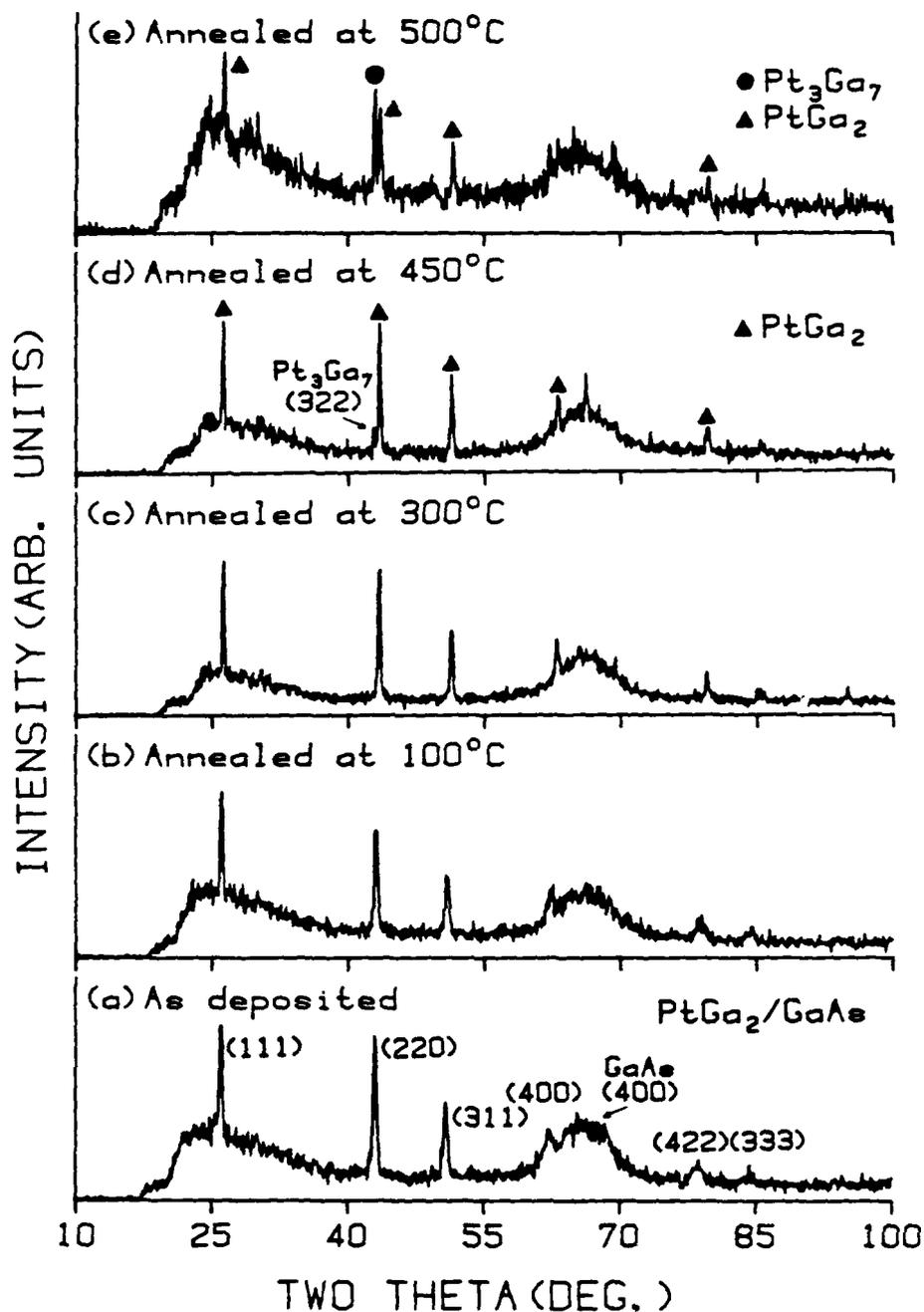


Fig. 5. XRD patterns of PtGa₂ thin films on GaAs (100) for (a) the as-deposited film and after the sample was annealed to (b) 100°C, (c) 300°C, (d) 450°C and (e) 500°C.

References

1. L. J. Brillson, *J. Phys. Chem. Solids* **44**, 703 (1983).
2. A. K. Sinha and J. M. Poate, in *Thin Films-Interdiffusion and Reactions*, edited by J. M. Poate, K. N. Tu and J. W. Mayor (Interscience, New York, 1978), chap. 11.
3. L. J. Brillson, *Surf. Sci. Rep.* **2**, 123 (1982).
4. C. T. Tsai and R. S. Williams, unpublished.
5. S. Kim, L. Hsu and R. S. Williams, *Phys. Rev. B* **36**, 3099, (1987).
6. JCPDS, Powder Diffraction File: Inorganic Phases (1987). International Center for Diffraction Data.
7. E. Hellner and F. Laves, *Z. Naturforsch.*, **2a**, 1947, 177-183.
8. Young K. Kim, David K. Shuh, R. S. Williams, Larry P. Sadwick and Kang L. Wang, unpublished.

ABSTRACTS DISTRIBUTION LIST, SOLID STATE & SURFACE CHEMISTRY

DL/1113/89/1

TECHNICAL REPORT DISTRIBUTION LIST, GENERAL

- Dr. J. Baldeschwieler
Chemistry & Chem Engrg
Calif Inst of Technology
Pasadena, CA 91125
- Dr. Paul G. Barbara
Department of Chemistry
University of Minnesota
Minneapolis, MN 55455-0431
- Dr. Duncan W. Brown
Adv. Technology Malls, Inc.
529-B Danbury Road
New Milford, CT 06776
- Dr. S. Bruckenstein
Department of Chemistry
State University of NY
Buffalo, NY 14214
- Dr. J. Butler
Naval Research Laboratory
Code 6115
Washington, DC 20375-5000
- Dr. R. P. H. Chang
Mats. Science & Engineering
Northwestern University
Evanston, IL 60208
- Dr. Paul A. Christian
Adv Chem. Technol., Fed. Systems
Eastman Kodak Company
Rochester, NY 14650-2156
- Dr. Richard Colton
Code 6170
Naval Research Laboratory
Washington, DC 20375-5000
- Dr. J. E. Demuth
IBM Watson Research Center
PO Box 218
Yorktown Heights, NY 10598
- Dr. F. J. DiSalvo
Department of Chemistry
Cornell University
Ithaca, NY 14853
- Dr. A. B. Ellis
Department of Chemistry
University of Wisconsin
Madison, WI 53706
- Dr. M. A. El-Sayed
Chemistry Department
University of California
Los Angeles, 90024 1569
- Dr. John Eyller
Department of Chemistry
University of Florida
Gainesville, FL 32611
- Dr. James F. Garvey
Department of Chemistry
State University of New York
Buffalo, NY 14214
- Dr. T. F. George
Chemistry/Physics Dept.
State University of New York
Buffalo, NY 14260
- Dr. Arvid Green
Quantum Surface Dynamics Br.
Naval Weapons Ctr. Code 3817
China Lake, CA 93555
- Dr. R. Hamers
IBM Watson Research Center
PO Box 218
Yorktown Heights, NY 10598
- Dr. Paul K. Hansma
Department of Physics
University of California
Santa Barbara, CA 93106
- Dr. C. B. Harris
Chemistry Dept.
University of California
Berkeley, CA 94720
- Dr. J. C. Hemminger
Chemistry Dept.
University of California
Irvine, CA 92717
- Dr. Roald Hoffmann
Chemistry Dept.
Cornell University
Ithaca, NY 14853
- Dr. L. Ingrante
Chemistry Dept.
Rensselaer Polytech. Inst.
Troy, NY 12181
- Dr. E. A. Irene
Chemistry Dept.
Univ. of North Carolina
Chapel Hill, NC 27514
- Dr. D. E. Irish
Department of Chemistry
University of Waterloo
ONT N2L 3G1, Canada
- Dr. Mark Johnson
Department of Chemistry
Yale University
New Haven, CT 06511
- Dr. Sylvia M. Johnson
SRI International
333 Ravenswood Avenue
Menlo Park, CA 94025
- Dr. Z. H. Kafafi
Optical Sci. Div. Code 6551
Naval Research Laboratory
Washington, DC 20375-5000
- Dr. George H. Morrison
Chemistry Dept.
Cornell University
Ithaca, NY 14853
- Dr. Daniel M. Neumark
Chemistry Department
University of California
Berkeley, CA 94720
- Dr. D. Ramaker
Chemistry Dept.
George Washington Univ.
Washington, DC 20052
- Dr. R. Reeves
Chemistry Dept.
Rensselaer Polytech. Inst.
Troy, NY 12181
- Dr. A. Reisman
Microelectronics Center
Research Triangle Park
No. Carolina, 27709
- Dr. G. Ruboff
IBM Watson Research Ctr.
PO Box 218
Yorktown Hgts, NY 10598
- Dr. Richard J. Saykally
Chemistry Department
University of California
Berkeley, CA 94720
- Dr. Robert W. Shaw
US Army Research Office
Res. Triangle Park, NC 27709
- Dr. S. Sibener
James Franck Institute
University of Chicago
Chicago, IL 60637
- Dr. R. E. Smalley
Department of Chemistry
Rice University, Box 1892
Houston, TX 77251
- Dr. G. A. Somorjai
Chemistry Dept.
University of California
Berkeley, CA 94720
- Dr. G. B. Stringfellow
Mats. Science & Engineering
University of Utah
Salt Lake City, UT 84112
- Dr. Galen D. Stucky
Chemistry Dept.
University of California
Santa Barbara, CA 93106
- Dr. H. Tachikawa
Chemistry Dept.
Jackson State University
Jackson, MI 39217
- Dr. W. Uenert
Surface Science & Technol. Lab
University of Maine
Orono, ME 04469
- Dr. R. P. Van Duyne
Chemistry Dept.
Northwestern University
Evanston, IL 60201
- Dr. David M. Walba
Chemistry Department
University of Colorado
Boulder, CO 80309-0215
- Dr. J. H. Weaver
Chemical Engrg & Mats. Sci.
University of Minnesota
Minneapolis, MN 55455
- Dr. B. R. Weiner
Department of Chemistry
University of Puerto Rico
Rio Piedras, PR 00931
- Dr. Robert L. Whetten
Chemistry Department
University of California
Los Angeles, CA 90024
- Dr. R. Stanley Williams
Dept. of Chemistry
University of California
Los Angeles, CA 90024
- Office of Naval Research
Chemistry Div., Code 1113
800 N. Quincy Avenue
Arlington, VA 22217-5000
- Chief of Naval Research
Spec. Assistant, Marine Corps
Code 00MC
800 N. Quincy Street
Arlington, VA 22217-5000
- Commanding Officer
Naval Weapons Support Center
Crane, IN 47522-5050
- Dr. Richard W. Drisko
Naval Civil Engineering Lab
Code L-52
Port Huenepe, CA 93043
- Defense Tech. Information Ctr.
Building 5
Cameron Station
Alexandria, VA 22314
- David Taylor Research Center
Attn: Dr. Eugene C. Fischer
Applied Chemistry Division
Annapolis, MD 21402-5067
- Dr. James S. Munday
Chemistry Div., Code 6100
Naval Research Laboratory
Washington, DC 20375-5000
- Dr. David Nelson
Office of Naval Res. Code 413
800 N. Quincy Street
Arlington, VA 22217-5000
- Dr. Ronald L. Atkins
Chemistry Div., Code 385
Naval Weapons Center
China Lake, CA 91553-6001
- Dr. Bernadette Eichinger
Naval Ships Systems Engrg Station
Phila. Naval Base, Code 051
Philadelphia, PA 19112
- David Taylor Research Station
Attn: Dr. H. H. Singerman
Code 283
Annapolis, MD 21402-5067
- Dr. Sachio Yamamoto
Naval Ocean Systems Center
Code 52
San Diego, CA 91212
- Carlota Leufroy
Office of Naval Research
1040 E. Green Street
Pasadena, CA 91106